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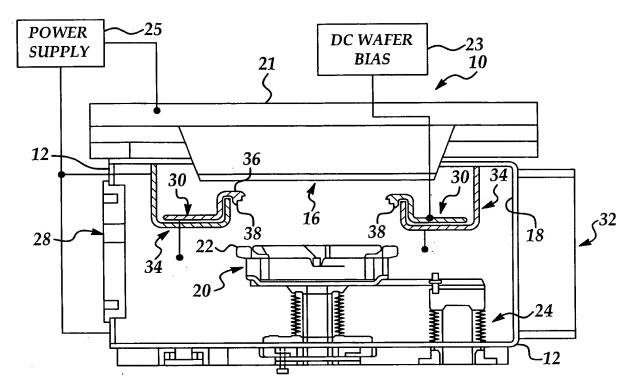
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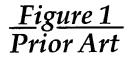
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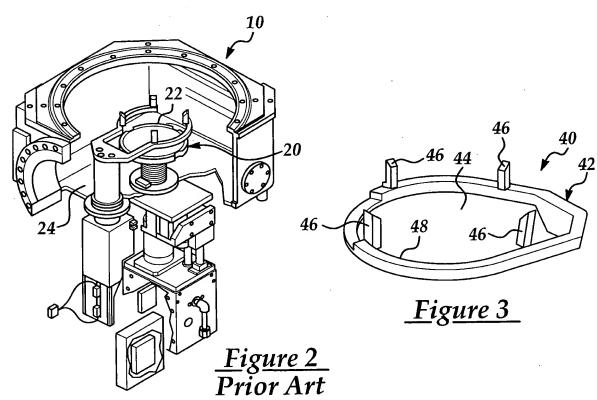
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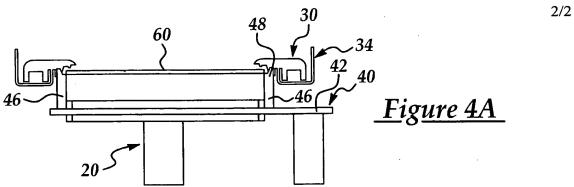


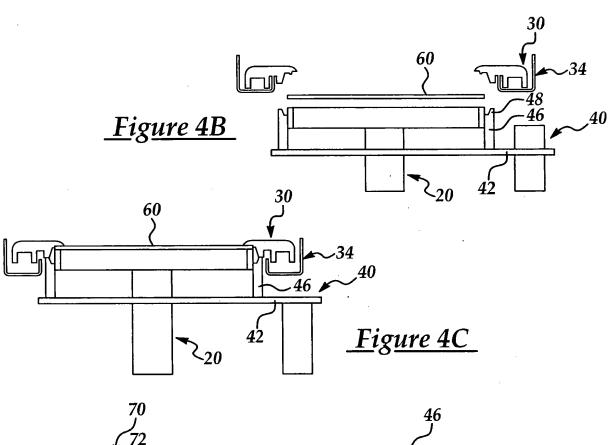
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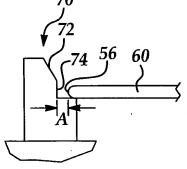
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<u>Figure 5A</u> Prior Art

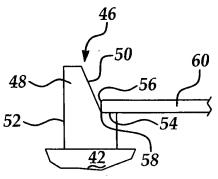


Figure 5B